

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-10 (Canceled).

Claim 11 (New): A deposit shield for use in a processing apparatus, in which a substrate to be processed is mounted on a stage serving as a lower electrode, and which is provided in a vacuum processing chamber wherein plasma processing using an upper electrode provided on the substrate is to be performed, the deposit shield comprising:

a side curved-surface portion which extends from a position lateral to a mounting surface of the stage to an outer periphery of the upper electrode, which is spaced apart from an outer periphery of the stage, and which has a flat inner surface located to surround the stage;

a notch portion located opposite to a carrier port which is provided at the processing chamber to allow the substrate to be carried out from and into the processing chamber, the notch portion being formed in a lower portion of the deposit shield;

a shutter including an end face which is shaped to be fitted to a cut end face of the notch portion such that the end face of the shutter and the side curved-surface portion have a continuously even and curved inner surface, the shutter functioning to maintain uniformity of a density of plasma generated in the plasma processing;

a raising/lower portion which raises/lowers the shutter when the substrate is carried out from and into the processing chamber;

an O-ring fitted in the end face of the shutter which is fitted to the cut end face of the notch portion; and

a spiral seal fitted in the end face of the shutter, located closer to an outer periphery of the shutter, and formed of metal to effect electrical conduction on the shutter.

Claim 12 (New): The deposit shield according to claim 11, in which the spiral seal causes the deposit shield and the shutter to be electrically connected to each other, so that the deposit shield and the shutter have the same potential, and also prevents the plasma generated in the process chamber from leaking from the deposit shield through a gap in the notch portion, which is present between the deposit shield and the shutter,

Claim 13 (New): The deposit shield according to claim 11, wherein a disk-shaped evacuation plate is provided around the stage, and when the shutter of the deposit shield is raised, the shutter and the evacuation plate are brought into contact with each other, and electrically connected to each other.

Claim 14 (New): The deposit shield according to claim 11, wherein the deposit shield and the shutter include respective heating mechanisms.

Claim 15 (New): The deposit shield according to claim 11, wherein:
the cut end portion of the notch portion and the end face of the shutter have respective L-shaped step portions which are fitted to each other;

an inner peripheral portion of the L-shaped step portion of the cut end portion of the notch portion extends, and an outer portion part of the L-shaped step portion of the end face of the shutter extends; and

plasma generated in the processing chamber is prevented from leaking between the notch portion and the end face of the shutter.